AMENDMENTS TO THE CLAIMS

Claim 1 (Currently Amended) A positive-working chemical-amplification photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) 100 parts by weight of a combination of a first copolymeric resin consisting of from 62 to 68% by moles of monomeric units (a) hydroxyl group containing styrene units, from 15 to 25% by moles of monomeric units (b) styrene units and from 12 to 18% by moles of monomeric units (c) acrylate or methacrylate ester units each having a solubility-reducing group capable of being eliminated in the presence of acid and a second copolymeric resin consisting of from 62 to 68% by moles of the monomeric units (a), from 25 to 35% by moles of the monomeric units (b) and from 2 to 8% by moles of the monomeric units (c) and;

wherein the first copolymeric resin is present in a weight ratio with respect to the second polymeric resin in the range from 9:1 to 5:5.

(B) from 1 to 20 parts by weight of a radiation-sensitive acid-generating agent which is an onium salt containing a fluoroalkyl sulfonate ion having 3 to 10 carbon atoms as the anion.

Claim 2 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the solubility-reducing group capable of being eliminated in the presence of an acid is selected from the group consisting of tertiary alkyl groups, 1-alkoxyalkyl groups and acetal groups.

Claim 3 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 2 in which the tertiary alkyl group is tert-butyl group.

Claim 4 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the component (B) is an onium salt compound containing a nonafluorobutane sulfonate ion as the anion.

Claim 5 (Previously Presented) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which each of the first and second copolymeric resins has a weight-average molecular weight in the range from 3000 to 30000.

Claim 6 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises:

(C) an amine compound selected from the group consisting of secondary amines and tertiary amines in an amount in the range from 0.001 to 10 parts by weight per 100 parts by weight of the component (A).

Claim 7 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises: (D) a carboxylic acid compound in an amount in the range from 0.001 to 10 parts by weight per 100 parts by weight of the component (A).

Claim 8 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 1 which further comprises dimethylacetamide in an amount in the range from 0.1 to 5.0% by weight based on the amount of the component (A).

Claim 9 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 1 in which the hydroxyl group-containing styrene unit as the monomeric unit (a) in the component (A) is a hydroxystyrene unit.

Claim 10 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 6 in which the amine compound is a tertiary alkanolamine.

Claim 11 (Original) The positive-working chemical-amplification photoresist composition as claimed in claim 7 in which the carboxylic acid compound is an aromatic carboxylic acid.

Claim 12 (Cancelled)